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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Celii et al. Art Unit: 1765  
 Serial No.: 09/599,718 Examiner: Brown, C.  
 Filing Date: 08/22/00 Docket No.: TI-29276  
 Title: PROCESS FLOW FOR DUAL DAMASCENE INTERCONNECT  
 STRUCTURES

Amendment under 37 CFR 1.115

Assistant Commissioner of Patents  
 Washington, DC 20231

**OFFICIAL**  
**FAX RECEIVED**  
 JUL 29 2002  
**GROUP 1700**

Dear Sir:

The following amendments and remarks are offered in response to the Examiner's Office Action dated 02/28/02. They are respectfully submitted as a full and complete response to that Action.

Please amend the above-referenced application as follows:

In the Claims:

Amend Claim 1 to read as follows:

1. (amended) A method of fabricating an integrated circuit, comprising the steps of:  
 forming an interlevel dielectric layer over a semiconductor body;  
 forming an intrametal dielectric layer over said interlevel dielectric layer;  
 forming a hardmask over said intrametal dielectric layer;  
 forming a via pattern over said hardmask;  
 selectively etching a via through said hardmask;  
 extending said via by selectively etching said intrametal dielectric layer;

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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Celii et al.  
Serial No.: 09/599,718

Art Unit: 1765  
Examiner: Brown, C.

Filing Date: 06/22/00

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Title: PROCESS FLOW FOR DUAL DAMASCENE INTERCONNECT  
STRUCTURES

**CERTIFICATION OF FACSIMILE TRANSMISSION**

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July 29, 2002

Jacqueline J. Garner, Reg. No. 36,144

Date

## FACSIMILE COVER SHEET

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<input type="checkbox"/> NEW APPLICATION	<input checked="" type="checkbox"/> EOT 2mth (3 Pages)
<input type="checkbox"/> DECLARATION (# Pages)	<input type="checkbox"/> NOTICE OF APPEAL (# Pages)
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NAME OF INVENTOR(S):	
Celii	
TITLE OF INVENTION:	
Process Flow for Dual Damascene Interconnect	
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TI-29276	20-0668
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